

SEARCHED

| Class | Sub. | Date | Exmr. |
|-------|------------------------|--------|-------|
| 356 | 399-4d | 4/1/03 | ✓m |
| 355 | 53,55 69,70 71 | | ✓ |
| 250 | 548 | ✓ | ✓ |
| 430 | 5,20, 22,30, 311 | ✓ | ✓ |

SEARCH NOTES (INCLUDING SEARCH STRATEGY)

| | Date | Exmr. |
|---|--------|-------|
| <u>EAST</u> resistance electrical & mask, reticle, target, wafer, substrate, dose exposure focus, develop sensitive intensity metrology angle, width, size. | 4/1/03 | ✓m |

INTERFERENCE SEARCHED

| Class | Sub. | Date | Exmr. |
|-------|------|------|-------|
| | | | |

(RIGHT OUTSIDE)